

0160-0193-0 PCT



#19/CB
8/27/2

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :

HIROSHI IKEDA ET AL

: EXAMINER: VANOY, T.

SERIAL NO: 09/463,961

: GROUP ART UNIT: 1754

FILED: MAY 25, 2000

: RCE FILED: HERewith

FOR: METHOD AND APPARATUS
FOR PROCESSING EXHAUST
GAS OF SEMICONDUCTOR
FABRICATION



RECEIVED
AUG 26 2002
TECHNOLOGY CENTER 1700

PRELIMINARY AMENDMENT AND REMARKS

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Further to the Notice of Appeal filed May 21, 2002, and in further response to the Final Rejection dated November 21, 2001, the period for response having been extended to August 21, 2002, by a petition for extension of time filed herewith, please amend the application identified above as follows (marked-up copy of amendments):

IN THE CLAIMS

Please amend Claim 1 as follows: